# DXRF012 RF VI Power Meter

Product Overview

DXRF012 RF VI power meter is an advanced instrument for real-time monitoring of parameters such as voltage, current, power, reflection, and impedance of RF Power Generator. With high accuracy and multiple functions, It can be used for testing RF Power Generator, Matching Box, and plasma related devices.

Product Features

- **Support measurement of 13.56 MHz, 27.12 MHz, and 40.68 MHz RF**
- **Support measurement of high-power RF up to 12kW**
- **Accurate measure for loads of 50Ω and non-50Ω with high-precision calibration**
- **Real time display curves of forward power, reflected power, voltage, current, load impedance and etc**
- **Sampling period ranges from 20 us to 1s for real-time mode**
- **Minimum sampling period can reach 1 us for high-speed mode, and the details of changes in pulse signals and arc discharge signals can be observed**
- **Real time display of impedance and trajectories on Smith charts, Rivals the Accuracy of offline vector network analyzer**
- **Equipped with Ethernet interface and R485 interface for easy system integration**

Monitoring software
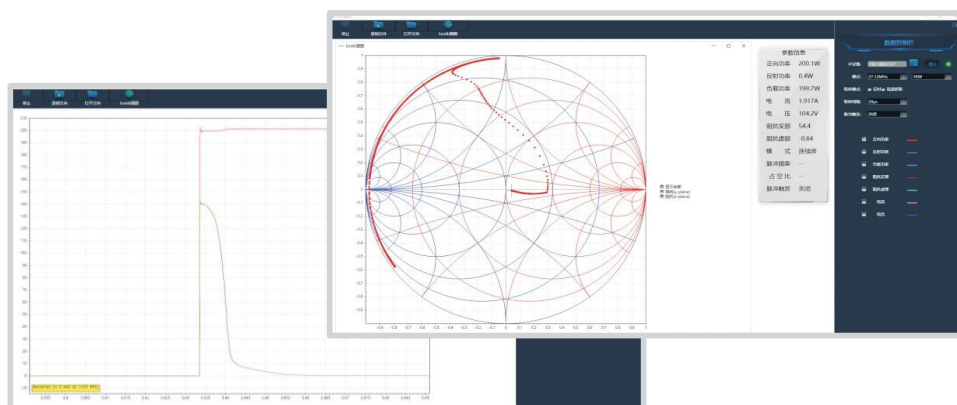
Tech Parameters

Items	Tech Parameters
Characteristic impedance	50Ω
RF connector	L 29, with adaptor to N type
Power range (50Ω impedance)	Up to 12 k W
Power Supply	12 V DC，2 A
Communication Interface	RJ 45 x 2，RS 485
Sampling period	1 us to 1 s
Power dynamic range	≥40 d B
Power measurement range	12 k W
Power resolution	0 . 1 W

Items	Tech Parameters
Power measurement accuracy	± 1 %
Voltage dynamic range	80 d B
Voltage measurement range	0 . 3 V to 3000 V RMS
Voltage resolution	0 . 1 V RMS
Voltage measurement accuracy	± 1 %
Current dynamic range	80 d B
Current measurement range	2 . 5 m A to 25 A RMS
Current resolution	1 . 0 m A
Current measurement accuracy	± 1 %

Applications
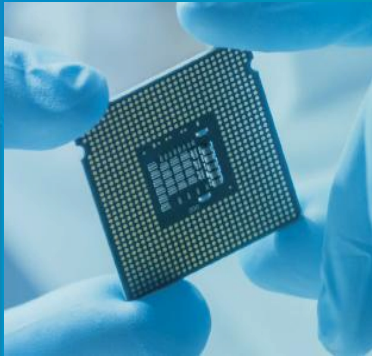
Semiconductor	Industrial	Medical
Wafer Cleaning	LED	Plasma Disinfection
Film Deposition	Solar Photovoltaic	Cancer Treatment
PVD/PECVD/ALD	Crystalline Silicon Coating	MRI
Magnetron Sputtering	Wear-protection layer	RF Cosmetology
Ion Beam Source	...	...
Ion Etching		
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